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LIQUID PHASE EPITAXY OF SEMICONDUCTING TIN ON INDIUM ANTIMONIDE

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พิมพ์ตั้นฉบับบทคัดย่อวิทยานิพนธ์ภายในกรอบสีเขียวนี้เพียงแผ่นเดียว

วิทยา อมรกิจบำรุง ซีพีแทกซีสภาวะ เหลว ของดีบุกกึ่งตัวนำบนอินเดียมแอนติโมไนด์ (LIQUID PHASE EPITAXY OF SEMICONDUCTING TIN ON INDIUM ANTIMONIDE อ.ที่ปรึกษา ศ.คร.วิรุฬท์ สายคณิต, ผศ.สมพงศ์ ฉัตราภรณ์, คร.วิโรจน์ ตันตราภรณ์, 112 หน้า.

ผลึกชนาดเล็กของดีบุกกึ่งตัวนำ สามารถเตรียมได้โดยวิธีอีพิแทกซีสภาวะเหลว จากสาร ละลายของดีบุกกับปรอทที่อุณหภูมิ 7.5 – 12.5 C บนแผนรองรับอินเดียมแอนติโมไนด์ หนา(111)B ที่เตรียมได้ผลึกชนาดเล็กนั้นเชื่อวาเพราะมีชั้นออกไซด์บนแผนรองรับอินเดียมแอนติโมไนด์ และมีรูขนาดเล็ก ทะลุชั้นออกไซด์ถึงแผนรองรับนั้น ได้ตรวจสอบผลึกดีบุกกึ่งตัวนำบนอินเดียมแอนติโมไนด์ ด้วยวิธีการ สะทอนกลับของรังสีเอ็กซ์ และวิธีวิเคราะหสารขนาดเล็กด้วยลำอิเลคตรอน (EPMA) ผลึกดีบุกกึ่งตัวนำ ที่ได้มีเสถียรภาพถึงอุณหภูมิประมาณ 60 C ซึ่งใกล้เคียงกับผลที่ได้โดยวิธีอีพิแทกซีจากลำโมเลกุล (MBE) จากผลงานผู้อื่น ตรวจสอบลักษณะของผลึกดีบุกกึ่งตัวนำด้วยกล้องจุลทรรศน์ธรรมดาและกล้องจุลทรรศน์ อิเลคตรอน (SEM)



ภาควิชา	ลายมือชื่อมิสิต ริกษ อนรถกระ	
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พิมพ์ตั้นฉบับบทคัดย่อวิทยานิพนธ์ภายในกรอบสีเขียวนี้เพียงแผ่นเดียว

VITTAYA AMORNKITBAMRUNG: LIQUID PHASE EPITAXY OF SEMICONDUCTING TIN ON INDIUM ANTIMONIDE. THESIS ADVISORS: PROF.VIRULH SA-YAKANIT, F.D.; ASSIST.PROF. SOMPHONG CHATRAPHORN, M.Sc.; WIROJANA TANTRAPORN, Ph.D. 112 PP.

Islets of α -Sn have been epitaxially grown by the Liquid Phase Epitaxy (LPE) technique on (111)B InSb substrate in Sn-Hg melt at 7.5-12.5°C. That epitaxial growths are in islet form is believed to be due to the presence of an oxide layer with pin-holes on InSb substrate. The x-ray back reflection technique and the Electron-Probe Micro Analysis (EPMA) were used to confirm α -Sn epitaxy on InSb. The α -Sn phase is stable to approximately 60°C, which is comparable to the results obtained by Molecular Beam Epitaxy (MBE) technique reported by other workers. The optical microscope and Scanning Electron Microscope (SEM) were used to evaluate the crystalization results.



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